



*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

In re PATENT APPLICATION of :  
Sang-Jun Choi : Group Art Unit: 1752  
Serial No.: 09/715,041 : Examiner: Yvette C. Thornton  
Filed: November 20, 2000 :

PHOTORESISTIVE POLYMER HAVING CYCLIC BACKBONE AND  
RESIST COMPOSITION CONTAINING THE SAME

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**AMENDMENT AND REQUEST FOR  
RECONSIDERATION**

U.S. Patent and Trademark Office  
**Customer Window, Mail Stop Amendment**  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314

Sir:

In response to the Office Action dated September 20, 2004, the Applicants submit the following remarks and arguments regarding the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.